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Advanced Processes Creating New Technologies in Tomorrow's Industry

Guest Editor

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Deadline for manuscript submissions:

closed (23 October 2022)

Message from the Guest Editor

This Special Issue aims to bring together topics including, but not limited to:

- 3-D printing;
- Sensors:
- Coatings;
- Catalysts;
- New materials;
- Chemically processes for new technologies in industry;
- Monitoring 3D objects (e.g., from additive manufacturing);
- Artificial Intelligence for process monitoring;
- Fault diagnosis and troubleshooting;
- Integration of statistical process control and engineering process control;
- Bioinspired Processes;
- Micro-Nano Machining TiO₂ Patterns;
- Photothermal Membrane of CuS/Polyacrylamide;
- Fabricating sub-100nm conducting polymer nanowires;
- Light-Trapping SERS Substrate with Regular;
- Fabrication of 3D biomimetic composite coating;
- Processes for robotics;
- Dynamic Processes;
- Industrial processes;
- Technical Processes.











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Message from the Editor-in-Chief

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